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-- PRESS RELEASE --

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## **SemEquip, Inc. to Introduce ClusterCarbon™ Implant Material at SEMICON Japan 2006**

**North Billerica, MA – December 1, 2006** - SemEquip®, an innovative leader in ion implantation sub-systems and advanced materials for semiconductor manufacturing, today announces that ClusterCarbon™ Implant Material for its ClusterIon® Source System technology will be introduced at SEMICON Japan 2006 (Booth # 2A-203) scheduled for December 6th through 8th at the Makuhari Messe, Chiba, Japan.

ClusterCarbon™ is a molecular carbon species for pre-amorphization implantation (PAI) and barrier to dopant diffusion for advanced source drain extension formation. ClusterCarbon™ replaces Germanium (Ge) PAI and monomer Carbon implant steps resulting in higher throughput and simpler process while utilizing existing Process of Record (POR) implant parameters. Furthermore, ClusterCarbon™ enables higher dopant activation and extremely abrupt, shallow junctions while extending the application life of conventional anneal processes.

“SemEquip continues to lead the industry by introducing ClusterCarbon™ for co-implantation with ClusterBoron® as a new process solution for 65nm, 45nm, and 32nm source drain extension.” said Brian Cohen, CEO and co-founder of SemEquip. “Smooth market introduction is ensured as ClusterCarbon™ works with ion implant platforms enabled with ClusterIon® Source technology.”

SemEquip’s ClusterIon® Source System provides up to 10x throughput gains for low-energy, high-dose implants compared to existing monomer implant platforms.

ClusterIon® Implant Materials are available from the Cluster Implant Material Alliance with ATMI. Jim Dietz, ATMI Director of Marketing, said, “Adding ClusterCarbon™ to ATMI's implant materials portfolio further enhances our commitment to improve process efficiency as we deliver measurable productivity increases to our customers' existing and new processes.”

### **About SemEquip, Inc.**

SemEquip, Inc. is a technology leader in the development of ion implantation systems and advanced ion source materials for the manufacture of logic and memory semiconductor devices. SemEquip’s technologies enable the utilization of cluster ion implantation for the manufacture of the world’s most advanced integrated circuits at the highest throughput and lowest cost. For additional information visit us at [www.semequip.com](http://www.semequip.com) or contact Brian Bernstein, VP – Sales & Marketing.